

SLOVENSKI STANDARD kSIST-TP FprCEN ISO/TR 5602:2022

01-september-2022

Viri napak pri uporabi elektrokemijske impedančne spektroskopije pri preiskavah premazov in drugih snovi (ISO/TR 5602:2021)
Sources of error in the use of electrochemical impedance spectroscopy for the investigation of coatings and other materials (ISO/TR 5602:2021)
Fehlerquellen bei der Anwendung elektrochemischer Elektroimpdanzspektroskopie bei der Untersuchung von Beschichtungen und anderer Stoffe (ISO/TR 5602:2021)
Sources d'erreur dans l'utilisation de la spectroscopie d'impédance électrochimique pour l'étude des revêtements et autres matériaux (ISO/TR 5602:2021)
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TECHNICAL REPORT



First edition 2021-11

Sources of error in the use of electrochemical impedance spectroscopy for the investigation of coatings and other materials

Sources d'erreur dans l'utilisation de la spectroscopie d'impédance électrochimique pour l'étude des revêtements et autres matériaux

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Foreword

ISO (the International Organization for Standardization) is a worldwide federation of national standards bodies (ISO member bodies). The work of preparing International Standards is normally carried out through ISO technical committees. Each member body interested in a subject for which a technical committee has been established has the right to be represented on that committee. International organizations, governmental and non-governmental, in liaison with ISO, also take part in the work. ISO collaborates closely with the International Electrotechnical Commission (IEC) on all matters of electrotechnical standardization.

The procedures used to develop this document and those intended for its further maintenance are described in the ISO/IEC Directives, Part 1. In particular, the different approval criteria needed for the different types of ISO documents should be noted. This document was drafted in accordance with the editorial rules of the ISO/IEC Directives, Part 2 (see www.iso.org/directives).

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For an explanation of the voluntary nature of standards, the meaning of ISO specific terms and expressions related to conformity assessment, as well as information about ISO's adherence to the World Trade Organization (WTO) principles in the Technical Barriers to Trade (TBT), see www.iso.org/iso/foreword.html.

This document was prepared by Technical Committee ISO/TC 35, *Paints and varnishes*, Subcommittee SC 9, *General test methods for paints and varnishes*.

Any feedback or questions on this document should be directed to the user's national standards body. A complete listing of these bodies can be found at <u>www.iso.org/members.html</u>.

Introduction

Electrochemical impedance spectroscopy is described in detail in ISO 16773-1 to ISO 16773-4. It became apparent during use of these standards that sources of error and measurement artefacts that lead to incorrect interpretations are not dealt with comprehensively. This document supplements the ISO 16773 series of standards to deal with this issue.

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TECHNICAL REPORT

Sources of error in the use of electrochemical impedance spectroscopy for the investigation of coatings and other materials

1 Scope

This document describes the main sources of error in the use of electrochemical impedance spectroscopy for the investigation of coatings and other materials. The sources of error listed here include all process steps from the set-up of the sample with the measuring cell right through to evaluation.

NOTE The sources of error discussed here do not represent a complete list.

2 Normative references

The following documents are referred to in the text in such a way that some or all of their content constitutes requirements of this document. For dated references, only the edition cited applies. For undated references, the latest edition of the referenced document (including any amendments) applies.

ISO 4618, Paints and varnishes — Terms and definitions

ISO 16773-1, Electrochemical impedance spectroscopy (EIS) on coated and uncoated metallic specimens — Part 1: Terms and definitions

3 Terms and definitions

For the purposes of this document, the terms and definitions given in ISO 4618, ISO 16773-1 and the following apply.

ISO and IEC maintain terminology databases for use in standardization at the following addresses:

- ISO Online browsing platform: available at <u>https://www.iso.org/obp</u>
- IEC Electropedia: available at <u>https://www.electropedia.org/</u>

3.1

limit impedance

minimum or maximum impedance that can be measured using the impedance spectrometer

3.2

limit frequency

minimum or maximum frequency that can be set on the impedance spectrometer

4 Error in the make-up of the measuring cell

4.1 Roughness of the surface

A wet and rough surface could conduct stray currents to a scratch or artificial defect, see <u>Figure 1</u>. This could yield in a spectrum showing a much lower resistance than in reality. Examples of spectra are shown in <u>Figure 2</u>.

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The rough surface was measured on the unscratched area. Although the rough surface was dried with a tissue, the residual amount of water was sufficient to produce a conductive path via the scratch to the substrate. As result, the spectrum of the sample resulted in the incorrect identification of a defective coating. After 2 h of continuous immersion in the cell, the surface outside the cell had dried and the conductive path was interrupted, which resulted in a typical spectrum of an intact coating.



4.2 O-ring — Considerations about the precise determination of the exposed area

If an O-ring is used to seal the cell, the exposed area is smaller than the theoretically assumed area because the O-ring will be compressed, and therefore, the exposed area will be reduced (see Figure 3).



a) Ideal situation, uncompressed



b) Real situation, compressed

Кеу

- R_0 radius of the uncompressed O-ring
- *a* difference in the radius of the O-ring due to compression

Figure 3 — Uncompressed and compressed O-ring

This behaviour can be visualized easily by using two transparent PMMA (poly methylene methacrylate) plates which were compressed with 4 screws. The screws were gently tightened only by hand and without any tools.

Figure 4 shows the set-up and Figure 5 and Figure 6 show the compressed O-rings of 1,2 cm and 5 cm diameter, respectively.



Figure 4 — Compression of O-ring using 4 screws

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Figure 5 — Compressed O-ring of 1,2 cm diameter



Figure 6 — Compressed O-ring of 5 cm diameter

The exposed area can be calculated as illustrated in Figure 7.



$$S_0 = \pi \cdot R_0^2$$

a) 0-ring not compressed — Contact surface of the specimen with testing solution



$$S_1 = \pi \cdot \left(R_0 - a\right)^2$$

b) O-ring compressed — Contact surface of the specimen with testing solution



$$\Delta S = S_0 - S_1 = \pi \cdot R_0^2 - \pi \cdot (R_0 - a)^2$$

c) Reduction of contact surface of specimen due to O-ring compression

Кеу

- S_0 geometric area with the O-ring uncompressed
- S_1 exposed area with the O-ring compressed
- ΔS difference $S_0 S_1$
- R_0 radius of the uncompressed O-ring
- *a* difference of the radius of the O-ring due to compression

Figure 7 — Calculation of the exposed area

The error d*S* between exposed area S_1 and geometric area S_0 can be approximated depending on the O-ring radius, R_0 , and the measured contact, 2a, using Formula (1):

$$dS = \frac{\Delta S}{S_0} \cdot 100 = \frac{2 \cdot a \cdot R_0 \cdot a^2}{R_0^2} \cdot 100$$
(1)

Some examples for calculation of the error of the exposed area are shown in <u>Table 1</u>.

Radius of the uncompressed O-ring	Difference in the radius of the O-ring due to compression		Geometric area with the O-ring uncompressed (theoretical surface)	Exposed area with the O-ring compressed (real surface)	Error of the exposed area
R_0	а	$R_0 - a$	S ₀	<i>S</i> ₁	d <i>S</i>
mm	mm	mm	mm ²	mm ²	%
6	0,8	5,2	113	85	25
12	0,8	11,2	452	394	13
24	0,8	23,2	1 809	1 690	7
30	0,8	29,2	2 826	2 677	5
6	1	5	113	79	31
12	1	11	452	380	16
24	1	23	1 809	1 661	8
30	1	29	2 826	2 641	7
6	1,25	4,75	113	71	37
12	1,25	10,75	452	363	20
24	1,25	22,75	1 809	1 625	10
30	1,25	28,75	2 826	2 595	8

Table 1 — Approximate error estimation of contact surface of specimens in corrosion cells

4.3 Faulty cell make-up

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4.3.1 Optically detectable leaks

Optically detectable leaks in the measuring cell are obvious and are not dealt with here.

4.3.2 Optically non-detectable causes st-tp-fprcen-iso-tr-5602-2022

The behaviour shown in Figure 8 was observed in a non-reproducible manner for a very welldocumented coating (cathodic e-coat) that is in familiar use in measurement technology. This behaviour occurred with varying amounts of pressure on the measuring cell at different locations on the same test panels; however, a direct relationship was not detected.

If the behaviour shown in Figure 8 is observed in a measuring cell, the measuring cell is not suitable.

Generally, every measurement set-up is tested for errors with a familiar system before this measuring cell is used on an unfamiliar system.